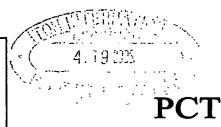
## PATENT COOPERATION TREATY

## From the INTERNATIONAL SEARCHING AUTHORITY

To: ITOH, Tadahiko

32nd Floor, Yebisu Garden Place Tower, 20-3, Ebisu 4-chome, Shibuya -ku, Tokyo 1506032 Japan



WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY (PCT Rule 43 bis. 1)

See paragraph 2 below

Date of mailing (day/month/year)

FOR FURTHER ACTION

18.04.2006

Applicant's or agent's file reference

International application No.

R05244PCT

International filing date (day/month/year)

19.12.2005

Priority date (day/month/year)

24.12.2004

International Patent Classification (IPC) or both national classification and IPC

Int.Cl. H01L27/088 (2006.01), H01L27/115 (2006.01), H01L29/788 (2006.01)

Applicant

RICOH COMPANY, LTD.

PCT/JP2005/023699

_								
1.	This c	pinion contains	indications relating to the following items:					
	Y	Box No. I	Basis of the opinion					
	<b>I</b>	Box No. II	Priority					
		Box No. III	Non-establishment of opinion with regard to novelty, inventive step and industrial applicability					
	Z	Box No. IV	Lack of unity of invention					
	Y	Box No. V	Reasoned statement under Rule 43 bis.1(a)(i) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement					
	<b></b> j	Box No. VI	Certain documents cited					
		Box No. VII	Certain defects in the international application					
		Вох №. VШ	Certain observations on the international application					
2.	FURT	THER ACTION						
	If a demand for international preliminary examination is made, this opinion will be considered to be a written opinion of the International Preliminary Examining Authority ("IPEA") except that this does not apply where the applicant chooses an Authority other than this one to be the IPEA and the chosen IPEA has notified the International Bureau under Rule 66.1bis(b) that written opinions of this International Searching Authority will not be so considered.							
	a writ	ten reply togeth	provided above, considered to be a written opinion of the IPEA, the applicant is invited to submit to the IPEA er, where appropriate, with amendments, before the expiration of 3 months from the date of mailing of Form are the expiration of 22 months from the priority date, whichever expires later.					

Date of completion of this opinion 28.03.200	28.03.2006				
Name and mailing address of the ISA/JP	Authorized officer	4M	9276		
	AKIRA SHOYAMA				
3-4-3, Kasumigaseki, Chiyoda-ku, Tokyo 100-8915, Japan	Telephone No. +81-3-3581-1101 Ext.	3462			

For further options, see Form PCT/ISA/220.

3. For further details, see notes to Form PCT/ISA/220.

# WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

International application No.

PCT/JP2005/023699

Βα	x No. I	Basis of the opinion
	337'41	
1.		gard to the language, this opinion has been established on the basis of:
		he international application in the language in which it was filed
		translation of the international application into, which is the language of a
	1	ranslation furnished for the purposes of international search (Rules 12.3(a) and 23.1(b)).
2.	With re	gard to any nuclectide and/or amino acid sequence disclosed in the international application and necessary to the
		d invention, this opinion has been established on the basis of:
	a. type	of material
		a sequence listing
		table(s) related to the sequence listing
	•	
	b. form	at of material
		оп рарет
	<b>.</b>	in electronic form
	c. time	of filing/furnishing
		contained in the international application as filed
		filed together with the international application in electronic form
		furnished subsequently to this Authority for the purposes of search
	F:	ramshed subsequently to this ruthority for the purposes of search
3.	f	n addition, in the case that more than one version or copy of a sequence listing and/or table(s) relating thereto has been iled or furnished, the required statements that the information in the subsequent or additional copies is identical to that n the application as filed or does not go beyond the application as filed, as appropriate, were furnished.
4.	Additio	nal comments:
	•	

# WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

International application No.

PCT/JP2005/023699

Bax No. IV	Lack of unity of invention
1. 🔀 In resp	oonse to the invitation (Form PCT/ISA/206) to pay additional fees the applicant has, within the applicable time limit:
₽i	paid additional fees
Г	paid additional fees under protest and, where applicable, the protest fee
Fi	paid additional fees under protest but the applicable protest fee was not paid
	not paid additional fees
• •	authority found that the requirement of unity of invention is not complied with and chose not to invite the applicant ditional fees.
3. This Author	rity considers that the requirement of unity of invention in accordance with Rule 13.1, 13.2 and 13.3 is
Con	plied with
rot	complied with for the following reasons:
D1: US	2003/0203575 Al (Hung et al.), 2003.10.30
	eparate inventions are not so linked as to form a single general ve concept for the following reasons:
claims transis realize is arra polysil floatin transis the mem is arra of poly a perip a peri semicor	same or corresponding matters (A) between the inventions of Nos. 1-22 are "a nonvolatile memory cell that includes a memory tor and a selection transistor, the memory transistor being d by a MOS transistor including a memory gate oxide film that nged on a semiconductor substrate and a floating gate made of icon that is arranged on the memory gate oxide film which agate in an electrically floating state, and the selection for being realized by a MOS transistor serially connected to ory transistor and including a selection gate oxide film that nged on the semiconductor substrate and a selection gate made silicon that is arranged on the selection gate oxide film; and heral circuit transistor realized by a MOS transistor including pheral circuit gate oxide film that is arranged on the iductor substrate, and a peripheral circuit gate made of icon that is arranged on the peripheral circuit gate oxide
apparer [ 0037], over the technic	ver, after taking the prior art into consideration, it became it that the matters (A) were mentioned in document D1, column figs.3-9. Therefore, the matters (A) makes no contribution e prior art. Thus there is no same or corresponding "special cal features" which is the expression in the PCT Rule 13.2. are, there is no technical relationship between the inventions ms Nos. [1-22].
	ntly, this opinion has been established in respect of the following parts of the international application:
🗹 all	parts .
☐ the	parts relating to claims Nos.

# WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

International application No.

PCT/JP2005/023699

Box No. V Reasoned statement under Rule 43bis. 1(a)(i) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

1. Statement			
Novelty (N)	Claims	2,5-22	YES
	Claims	1,3,4	NO
Inventive step (IS)	Claims		YES
	Claims	1-22	NO NO
Industrial applicability (IA)	Claims	1-22	YES
	Claims		NO

#### 2. Citations and explanations:

D1:US 2003/0203575 A1 (Hung et al.) 2003.10.30,

D2:US 2003/0235082 A1 (Hsu et al.) 2003.12.25,

D3:JP 2003-347435 A (RICOH KK) 2003.12.05,

D4:US 5925907 A (Hazama) 1999.07.20,

#### [Claims 1, 3, 4]

The subject matter of claims 1, 3, 4 does not appear to be novel with respect to D1. The matters of "the memory gate oxide film is arranged to be thinner than the peripheral circuit gate oxide film" appears to be known from D1 (see column [ 0037] , figs.3-9).

### [Claims 12-18]

The subject matter of claims 12-18 does not appear to involve an inventive step in view of D1 and D4. D4 discloses that an impurity concentration within the polysilicon of the floating gate is arranged to be lower than an impurity concentration within the polysilicon of the peripheral circuit gate oxide film(see column 6, line 59-column 7, line 18, figs.1A-2B).

#### [Claims 2, 19]

The subject matter of claims 2, 19 does not appear to involve an inventive step in view of D1, D4 and D2. D2 discloses that the memory transistor and the selection transistor are PMOS transistors (see column figs.3A, 3B, 4).

### [Claims 5-11, 20-22]

The subject matter of claims 5-11, 20-22 does not appear to involve an inventive step in view of D1, D4 and D3. D3 discloses that "the floating gate and the lower electrode are created from a same polysilicon layer, and the capacitor insulating film is arranged on an upper surface and a side surface of the floating gate", "a divider resistor circuit" with "a plurality of fuse MOS transistors", and etc. (see figs.5,6).